

Joint International Conference on The 8th ICMAP & The 9th ISFM

January 17-20, 2021 | Online Conference

[TB4] Plasma Diagnostics and Process Monitoring Technology I	
Date / Time	January 19 (Tue.), 2021 / 16:30-18:10
Place	Channel B
Session Chair(s)	Se Youn Moon (Jeonbuk Nat'l Univ., Korea)

[TB4-1]

16:30-16:50

Understanding Electron Power Absorption in CCPs via a Boltzmann Term Analysis as a Basis for Knowledge-Based Process Development

Mate Vass¹, Sebastian Wilczek¹, Trevor Lafleur², Ralf Peter Brinkmann¹, Zoltan Donko³, and Julian Schulze¹

¹Ruhr Univ. Bochum, Germany, ²PlasmaPotential-Physics Consulting and Research, Australia, ³Wigner Research Centre for Physics, Hungary

[TB4-2]

16:50-17:10

Conversion of Volatile Organic Compounds in a Twin Surface Dielectric Barrier Discharge

Lars Schücke, Jan-Luca Gembus, Niklas Peters, Friederike Kogelheide, Ryan T. Nguyen-Smith, Andrew. R. Gibson, Julian Schulze, Peter Awakowicz, and Martin Muhler

Ruhr Univ. Bochum, Germany

[TB4-3]

17:10-17:30

Application of PI-VM to Develop Automatic Process Controller (PI-APC) for Si Etching Processes

Sangwon Ryu, Ji-Won Kwon, Jihoon Park, Ingyu Lee, and Gon-Ho Kim

Seoul Nat'l Univ., Korea

[TB4-4]

17:30-17:50

Development of Si Etch Profile Virtual Metrology using Plasma Information(PI-VM) in SF₆/O₂/Ar Capacitively Coupled Plasma

Ji-Won Kwon¹, Sangwon Ryu¹, Jihoon Park¹, Haneul Lee¹, Yunchang Jang¹, Seolhye Park², and Gon-Ho Kim¹

¹Seoul Nat'l Univ., Korea, ²Samsung Display Co., Ltd., Korea

[TB4-5]

17:50-18:10

Extracting Electron Neutral Collision Frequency from Impedance Characteristics of Magnetized Capacitive Coupled RF Discharge

Shikha Binwal¹, Jay K Joshi², Shantanu Kumar Karkari², and Lekha Nair¹

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